

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2003-160620

(43)Date of publication of application : 03.06.2003

(51)Int.Cl.

C08F232/08  
C08F 4/00  
C08F 4/70  
C08F 8/12  
C08F234/02  
C08F236/00  
C08J 5/18  
C08J 7/00  
C08K 3/16  
C08K 3/22  
C08K 5/00  
C08L 45/00  
C08L 47/00  
G02B 1/04  
G02B 1/11  
G02B 5/30  
G02B 6/00

(21)Application number : 2001-336593

(71)Applicant : JSR CORP

(22)Date of filing : 01.11.2001

(72)Inventor : OSHIMA NOBORU  
MARUYAMA YOICHIRO  
KAIZU MITSUTAKA  
HAYASHI TOSHIHITO  
OKITA KENZO

(30)Priority

Priority number : 2001277847 Priority date : 13.09.2001 Priority country : JP

(54) CYCLOOLEFIN BASED ADDITION COPOLYMER, ITS COMPOSITION FOR  
CROSSLINKAGE, ITS CROSSLINKED SUBSTANCE, OPTICALLY TRANSPARENT MATERIAL,  
AND METHOD FOR MANUFACTURING CYCLOOLEFIN BASED ADDITION COPOLYMER

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a cycloolefin based addition copolymer that contains a reactive silyl group having a specific structure, has excellent optical transparency, heat resistance and adhesiveness, and can produce crosslinked substance having improved dimensional stability, solvent and chemicals resistance by crosslinking.

SOLUTION: The cycloolefin based addition copolymer containing the reactive silyl group that is made by addition polymerization between a cycloolefin compound having the reactive silyl group such as 5-[1',4',4'-trimethyl-2',6'-dioxo-1'-silacyclohexyl]-bicyclo[2.2.1]hepto-2-en and other cycloolefin compound such as bicyclo[2.2.1]hepto-2-en, a composition for crosslinkage made by combining with a specific crosslinking agent, the crosslinked substance made by crosslinking the composition, an optical material containing the copolymer, the composition or the crosslinked substance.

LEGAL STATUS

[Date of request for examination] 18.03.2004  
[Date of sending the examiner's decision of rejection]  
[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]  
[Date of final disposal for application]  
[Patent number]  
[Date of registration]  
[Number of appeal against examiner's decision of rejection]  
[Date of requesting appeal against examiner's decision of rejection]  
[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office